

ABSTRACT OF THE DISCLOSURE

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An exposure apparatus for sequentially performing exposure of device patterns provided in a pattern effective area of a photo-mask (10) on to shot areas of a wafer (20), to provide excellent throughput performance, includes an illumination unit (115) for collectively illuminating the entire pattern effective area of the photo-mask contained within the illumination range with exposure light, a mask stage (114) that moves the photo-mask for the illumination range in the mask scanning direction, a wafer stage (111) that moves the wafer for the projection range in which the pattern effective area of the photo-mask is projected in the wafer scanning direction and a control unit (140) for, after containing at least one shot area of the wafer within the projection range to perform exposure of device patterns provided in the pattern effective area of the photo-mask on to the one shot area of the wafer, synchronizing and controlling the movements of the mask stage and the wafer stage while keeping the entire pattern effective area of the photo-mask contained within the illumination range.